

IN THE CITY OF NEW YORK COLUMBIA NANO INITIATIVE / CENTER FOR INTEGRATED SCIENCE AND ENGINEERING

Yield Engineering Systems (YES) Vapor Priming System



These instructions are intended for reference only, and will *not* replace the thorough training required for proper system operation. Contact a clean room staff member with questions or to report a system problem.

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Overview:

The YES (Yield Engineering Systems) Vapor Priming System is used to prepare substrates for optimal photoresist/electron beam resist coating. The instrument de-hydrates surfaces and deposits an ultra-thin coating of hexamethyldisilazane molecules from the vapor phase, which bond strongly to silicon oxide surfaces. The methyl groups in the tail portion of the molecule produce a stable hydrophobic surface that is ideal for uniformly applying photoresist.

- 1. Enable the tool YES (HMDS) Oven in BADGER
- 2. Check vacuum in main chamber.

The main chamber gauge should indicate pressure < 10 torr.



Check the HMDS fill level and vacuum inside the vacuum flask, on the left side of the tool. Pressure inside the flask should be < -85 kPa (-25 in. Hg).

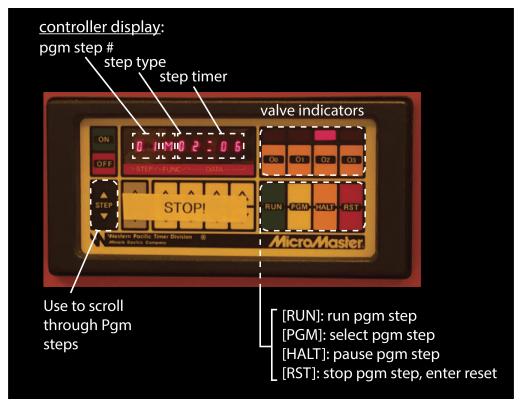
If no HMDS is found in the flask or if the pressure exceeds these guidelines, contact staff.





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3. YES Oven Controller operation:



The YES Oven controller performs sequences for chamber pumping, venting, HMDS processing, and HMDS flask filling (staff only).

The following table shows the program and the first step number:

Program name	1 st program step #	Description
Chamber vent	#3	Vents main chamber with N ₂ by
		opening valve "O1"
Chamber pump	#1	Pumps main chamber by opening
		vacuum valve "O2"
HMDS prime	#5	Begins HMDS processing
process		sequence
Chamber and flask pump	Staff-only	Pumps main chamber and
		vacuum flask by opening vacuum
		valve "O2" and flask valve "O3"

DO NOT CHANGE PARAMETERS UNDERNEATH DISPLAY!



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- 4. Vent the oven using the vent program (Program #3).
 - Press [PGM] key
 - Use Pgm step selector [STEP] to select **Program #3**
 - Press [RUN]

The O1 valve will open, backfilling the chamber with N_2 . Unlatch the front door to prevent over pressurizing the chamber.

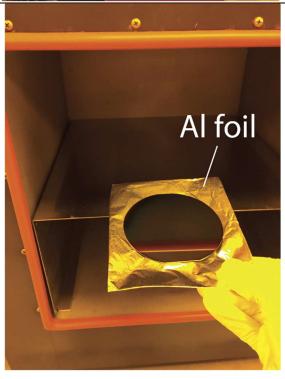
Chamber typically fully vents *before* timer elapses. Door may be opened for loading samples.





5. Load sample:

- Place wafer/samples inside the oven
- Samples may be supported on Aluminum foil, stainless steel or glass/quartz carriers.
- Teflon or other plastic carriers are not allowed.
- HMDS vapor priming is a conformal coating process.
 Line-of-sight is not required for successful coating.





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6. Begin Pre-programmed HMDS process (Program #5):

- If prior vent step timer has not elapsed, press the [RST] key to enter RESET mode.
- Press [PGM] key
- Use Pgm step selector, [STEP], to select **Program #5**
- Press [RUN] process takes ~ 35 minutes to complete

The following process will now run:

- *Surface dehydration*:
 - o Controller perform three cycles of chamber evacuation and N₂ backfill at 155-160°C, thus preparing the surface for reaction with HMDS.
- HMDS Vaporization:
 - Once below the HMDS vapor pressure setpoint, the controller pulses open the valve to the HMDS vacuum flask.
 - While open, HMDS vaporizes and molecules fill the chamber in the gas phase.
 - o HMDS molecules react with oxide surfaces and form a stable and directional bond.
- Chamber purge:
 - Controller pumps the chamber of residual HMDS vapor and performs one cycle of N₂ purge. A final N₂ backfill brings the chamber to atmospheric pressure.

Note: If users would like to change the YES Oven program, please contact staff at cnicleanroom@columbia.edu.



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- 7. Remove sample from chamber.
 - Use caution, as sample will be ~150°C.
- **8. Pump down** the chamber to leave for the next user (**Program #1**):
 - Close chamber door and latch
 - If prior vent step timer has not elapsed, press the [RST] key to enter RESET mode.
 - Press [PGM] key
 - Use Pgm step selector [STEP] to select **Program #1**
 - Press [RUN] and ensure main chamber is pumping down before leaving tool.
- 9. BADGER LOGOUT:
 - Disable the YES (HMDS) Oven in **BADGER** when finished.